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**AMENDMENTS TO THE CLAIMS** 

This listing of claims will replace all prior versions and listings of claims in the

application:

LISTING OF CLAIMS:

1. (original): A gas barrier film having an inorganic coating layer formed by the sol-gel

method or an organic-inorganic hybrid coating layer formed by the sol-gel method on a

transparent base film having a glass transition temperature of 100°C or higher and a linear

thermal expansion coefficient of 40 ppm/°C or lower.

2. (original): The gas barrier film according to claim 1 having an organic-inorganic

hybrid coating layer formed by the sol-gel method on a transparent base film having a glass

transition temperature of 100°C or higher and a linear thermal expansion coefficient of 40

ppm/°C or lower.

3. (original): The gas barrier film according to claim 1 having an inorganic coating

layer formed by the sol-gel method and an organic-inorganic hybrid coating layer formed by

the sol-gel method on a transparent base film having a glass transition temperature of 100°C

or higher and a linear thermal expansion coefficient of 40 ppm/°C or lower.

4. (original): The gas barrier film according to claim 1 having an inorganic thin film

layer and an organic-inorganic hybrid coating layer formed by the sol-gel method on a

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transparent base film having a glass transition temperature of 100°C or higher and a linear thermal expansion coefficient of 40 ppm/°C or lower.

5. (original): The gas barrier film according to claim 4, wherein the inorganic thin film

layer is an inorganic coating layer formed by the sol-gel method.

6. (original): The gas barrier film according to claim 1, wherein the base film has a

glass transition temperature of 120°C or higher.

7. (original): The gas barrier film according to claim 1, wherein the base film has a

glass transition temperature of 150°C or higher.

8. (original): The gas barrier film according to claim 1, wherein the base film has a

linear thermal expansion coefficient of 20 ppm/°C or lower.

9. (original): The gas barrier film according to claim 1, wherein the base film is made

of a material selected from the group consisting of polyethylene naphthalate, polycarbonate,

cycloolefin polymer, polyalylate and polyethersulfone.

10. (original): The gas barrier film according to claim 1, wherein the base film

contains an inorganic layered compound.

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11. (original): The gas barrier film according to claim 10, wherein the weight ratio of the inorganic layered compound and a resin contained in the base film is preferably 1/100

to 100/20.

12. (original): The gas barrier film according to claim 10, wherein the inorganic

layered compound contains an organic cation.

13. (original): The gas barrier film according to claim 12, wherein the organic cation

contains alkylammonium ions containing a long-chain alkyl group.

14. (original): The gas barrier film according to claim 12, wherein the organic cation

is contained in an amount of 0.05 to 3 equivalents relative to the cation exchange capacity of

the inorganic layered compound.

15. (currently amended): 15. The gas barrier film according to claim 12, wherein the

base film has a laminated structure of having an inorganic thin film layer and organic-inorganic

hybrid coating layer formed by the sol-gel method on the base film.

16. (original): A substrate for a display having the gas barrier film according to

Claim 1.

17. (original): A display device having the gas barrier film according to claim 1.

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18. (original): An organic electroluminescent device having the gas barrier film according to claim 1.

19. (original): A liquid crystal device having the gas barrier film according to claim 1.

20. (original): A method for preparing a gas barrier film having an inorganic coating layer or an organic-inorganic hybrid coating layer on a transparent base film having a glass transition temperature of 100°C or higher and a linear thermal expansion coefficient of 40 ppm/°C or lower, which comprises the step of forming the inorganic coating layer on the transparent base film by hydrolizing and polycondensating a metal alkoxide, or the step of forming the organic-inorganic hybrid coating layer on the transparent base film by hydrolizing and polycondensating a metal alkoxide in the presence of a resin.

21. (original): A method for preparing a gas barrier film having an inorganic coating layer and an organic-inorganic hybrid coating layer on a transparent base film having a glass transition temperature of 100°C or higher and a linear thermal expansion coefficient of 40 ppm/°C or lower, which comprises the step of forming the inorganic coating layer on the transparent base film by hydrolizing and polycondensating a metal alkoxide, and the step of forming the organic-inorganic hybrid coating layer on the transparent base film by hydrolizing and polycondensating a metal alkoxide in the presence of a resin.